

B1  
H11-109888A, and Japanese patent H11-130471A).

Delete page 4, lines 7-10, and add, as follows:

B2  
The glass article of the present invention has an alkali-containing glass substrate, and a barrier film formed on a surface of the alkali-containing glass substrate for preventing diffusion of metal ions. The barrier film mainly consists of indium oxide and/or tin oxide.

Delete page 4, line 20 to page 5, line 7, and add, as follows:

B3  
That is, when the diffusion barrier film is formed by a physical vapour deposition method such as a sputtering method, an ion plating method, or a vacuum evaporation method, alkali is diffused in a trace amount from the glass during the film formation and the diffusion of alkali may affect the crystal structure of the barrier film. In case of a large amount of diffused alkali, the crystal structure of the barrier film is deteriorated so that the barrier film becomes porous, thus decreasing the efficiency of preventing the diffusion of metal ions.

Delete page 5, line 14 to page 6, line 5, and add, as follows:

B4  
When the barrier film is formed by a chemical vapour deposition (CVD) method such as a chemical gaseous phase deposition method, the same phenomenon as the case of using the physical vapour deposition method occurs. When the barrier film is formed by the CVD method, source material used in the method generally contains chlorine so that the material liberates the chlorine during the film formation and the chlorine reacts with alkali ingredient contained in the glass substrate so as to deposit chlorine compounds on the glass substrate. Portions where the chlorine compounds are formed do not allow the formation of the above barrier film mainly consisting of indium oxide and/or tin oxide so that the barrier film has pin holes. The diffusion of metal ions can not be prevented at such portions.

Delete page 9, line 4, and add, as follows:

B5  
The barrier film 2 mainly consists of  $\text{In}_2\text{O}_3$  and/or  $\text{SnO}_2$ .